

*SPECIFICATION AMENDMENTS*

Replace the paragraph beginning at page 2, line 30 with:

Fig. 1 of JP-A-5-299406 shows a proposed substrate cleaning bath which cleans a substrate by causing a cleaning fluid supplied from a cleaning fluid supply port of the substrate cleaning bath to flow ~~in a horizontal direction of~~ parallel to the substrate through use of a straightening vane. JP-A-5-21413 also describes a proposed cleaning apparatus and method for cleaning a semiconductor substrate by causing a chemical to flow in parallel through use of a slit wall surface. However, these publications fail to describe a chemical processor and a chemical processing method for use with blind holes.